

IN THE CLAIMS:

Please amend claims 1-20 as follows:

1. (Currently Amended) ~~Method~~ A method for producing a superconducting inductive component having at least two plots, ~~this said~~ component comprising at least one line segment incorporating at least one plot of the component, ~~this said~~ line segment constituting a conducting or superconducting layer within a stack (E) of alternately superconducting (C1) and insulating (C2) films.

2. (Currently Amended) ~~Method~~ The method according to claim 1, ~~characterized in that~~ wherein each film constituting the stack (E) is perfectly crystallized.

3. (Currently Amended) ~~Method~~ The method according to ~~one of~~ claim 1, ~~characterized in that it comprises~~ further including a prior step of depositing an insulating film (C2) on a substrate (S).

4. (Currently Amended) ~~Method~~ The method according to ~~one of~~ claim 1, ~~characterized in that it comprises~~ further including a prior step of depositing a superconducting film (C1) on a substrate (S).

5. (Currently Amended) ~~Method~~ The method according to ~~one of~~ claims ~~1 or 2~~ claim 1, characterized in that it comprises further including a prior step of depositing a superconducting film (~~L1~~) on a substrate (~~S~~) followed by the depositing of the stack (~~E~~).

6. (Currently Amended) ~~Method~~ The method according to ~~one of~~ claims ~~3 or 4~~ claim 3, characterized in that it comprises ~~moreover~~ further including the following steps:

- a deposit of the stack (~~E~~) of alternately superconducting (~~C1~~) and insulating (~~C2~~) films,
- an etching of the stack (~~E~~) carried out in such a way that the latter only remains at the locations where an inductive component is to be implanted.

7. (Currently Amended) ~~Method~~ The method according to claim 5, characterized in that it comprises ~~moreover~~ further including the following steps:

- an etching of the stack (~~E~~) carried out in such a way that the latter only remains at the locations where an inductive component is to be implanted.
- an etching of the superconducting film (~~L1~~).

8. (Currently Amended) ~~Method~~ The method according to claim 5, characterized in that it comprises ~~moreover~~ further including the following steps:

- a simultaneous etching of the stack (~~E~~) and of the superconducting film (~~L1~~)
- an etching of the stack (~~E~~) carried out in such a way that the latter only remains at the locations where an inductive component is to be implanted.

9. (Currently Amended) ~~Method~~ The method according to ~~one of the preceding claims~~, characterized in that claim 1, wherein at least one of the superconducting films (~~C1~~) is produced from $\text{YBa}_2\text{Cu}_3\text{O}_{7-\delta}$ compounds.

10. (Currently Amended) ~~Method~~ The method according to ~~one of the preceding claims~~, characterized in that claim 1, wherein at least one of the insulating films (~~C2~~) is made from LaAlO_3 compounds.

11. (Currently Amended) ~~System~~ A system for producing a superconducting inductive component having at least two plots, ~~this said~~ component comprising at least one line segment incorporating at least one plot of the component, ~~this said~~ line segment constituting a conducting or superconducting layer within a stack (~~E~~) of alternately superconducting (~~C1~~) and insulating (~~C2~~) films, implementing the method according to ~~one of the preceding claims~~ claim 1.

12. (Currently Amended) ~~System~~ The system according to claim 11, characterized in that it comprises further including:

- means for depositing a stack (~~E~~) of alternately superconducting and insulating films, and

- means for etching all of the deposited films, ~~these said~~ means being arranged in such a way that said deposited films remain only at the locations where an inductive component is to be implanted.

13. (Currently Amended) ~~System~~ The system according to claim 11, characterized in that it comprises further including:

- means for depositing a superconducting film (~~L1~~) on a substrate (~~S~~),

- means for depositing on the superconducting film (~~L1~~) a stack (~~E~~) of alternately superconducting and insulating films, and

- means for etching all of the deposited films, these means being arranged in such a way that the film (~~L1~~) remains only at the locations where a superconducting line is to be implanted and the stack (~~E~~) remains only at the locations where an inductive component is to be implanted.

14. (Currently Amended) ~~Antenna~~ An antenna device comprising an electronic circuit including a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.

15. (Currently Amended) ~~Antenna~~ The antenna device according to claim 14, ~~characterized in that~~ wherein the antenna is produced from a superconducting thin film.

16. (Currently Amended) ~~Delay~~ A delay line device comprising an inductive component in ~~serie~~ series and a capacitive component in parallel downstream of said inductive component, ~~characterized in that~~ wherein the inductive component is a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.

17. (Currently Amended) ~~Phase~~ A phase shift radar device comprising a plurality of antennas each comprising an electronic circuit including a delay line according to claim 16, ~~this said~~ the said delay line being arranged such that each of said antennas transmits a signal whose phase is shifted with respect to that of the near antennas.

18. (Currently Amended) ~~Electronic~~ An electronic frequency filtering device comprising an electronic circuit including a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.

19. (Currently Amended) ~~High-pass~~ A high-pass filter device comprising an inductive component in parallel and a capacitive component in serie-series downstream of said inductive component, ~~characterized in that~~ wherein the inductive component is a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.

20. (Currently Amended) ~~Low-pass~~ A low-pass filter device comprising a capacitive component in parallel and an inductive component in serie-series downstream of said capacitive component, ~~characterized in that~~ wherein the inductive component is a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.